



DOCKET NO: 247866US2S

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF

AKIRA HOKAZONO, ET AL.

SERIAL NO: 10/759,205

FILED: JANUARY 20, 2004

FOR: SEMICONDUCTOR DEVICE
HAVING METAL SILICIDE FILMS
FORMED ON SOURCE AND DRAIN
REGIONS AND METHOD FOR
MANUFACTURING THE SAME

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: EXAMINER: MAGEE, T.

:

: GROUP ART UNIT: 2811

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AMENDMENT

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313

SIR:

In response to the Office Action dated December 20, 2004, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 9 of this paper.